

International conference on  
Extended defects in semiconductors, Göttingen 2014

# Dislocation clusters in multicrystalline silicon

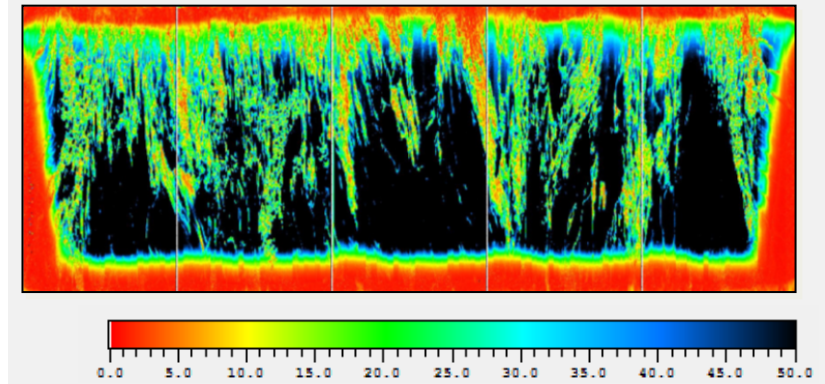
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Lamine Sylla, Winfried Seifert, Martin Kittler, Jan Bauer



# Introduction

Multicrystalline silicon grown by directional solidification is the mainstream in PV industry due to low cost of ownership and high throughput.

Microwave-detected photoconductivity



Minority carrier lifetime ( $\mu\text{s}$ )

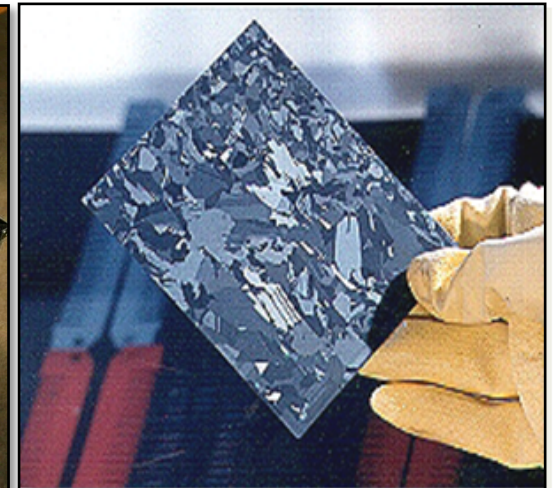
Ingots



Bricks

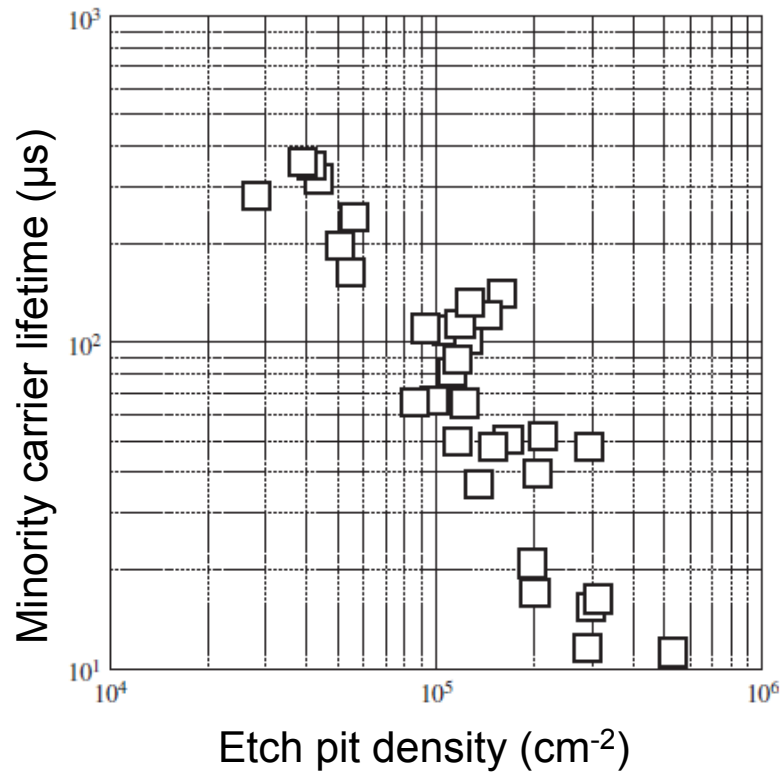


Wafers



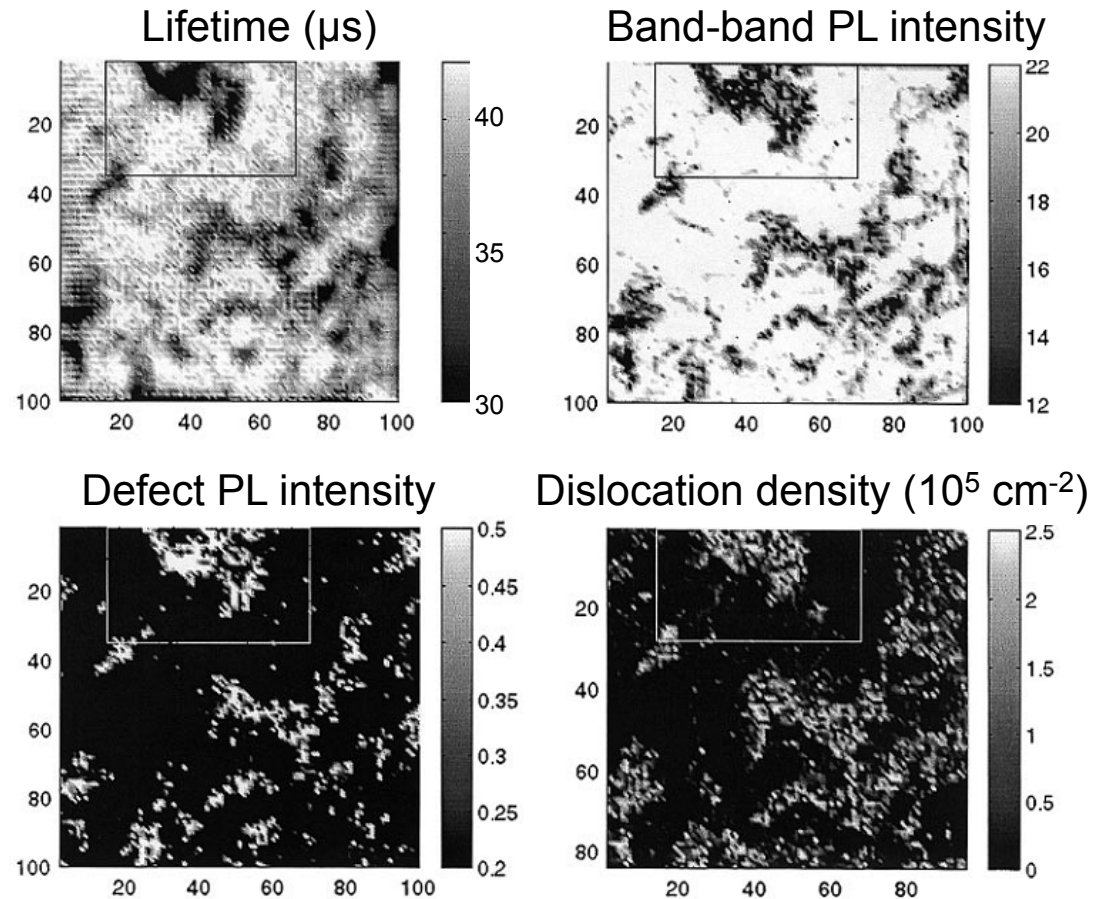
# Dislocation issues in mc Si

## Minority carrier lifetime vs etch pit density



[Arafune 2006]

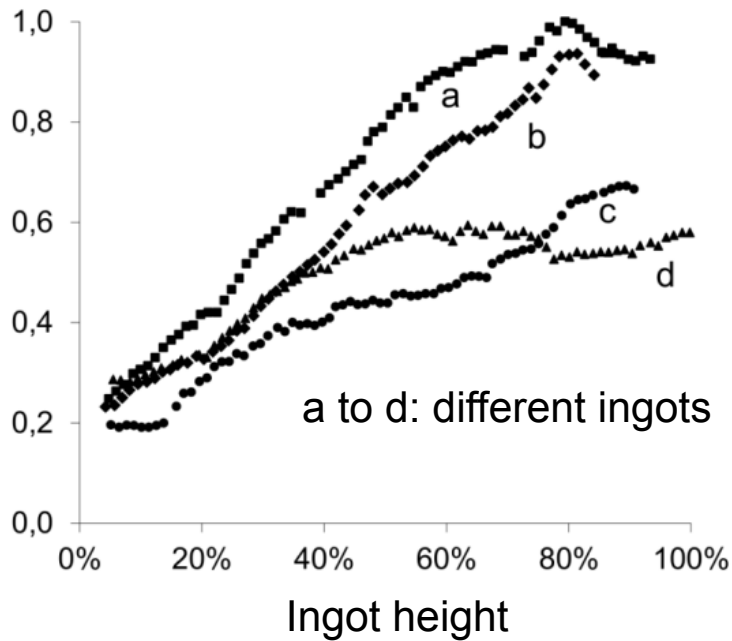
## Carrier lifetime, photoluminescence and dislocation density



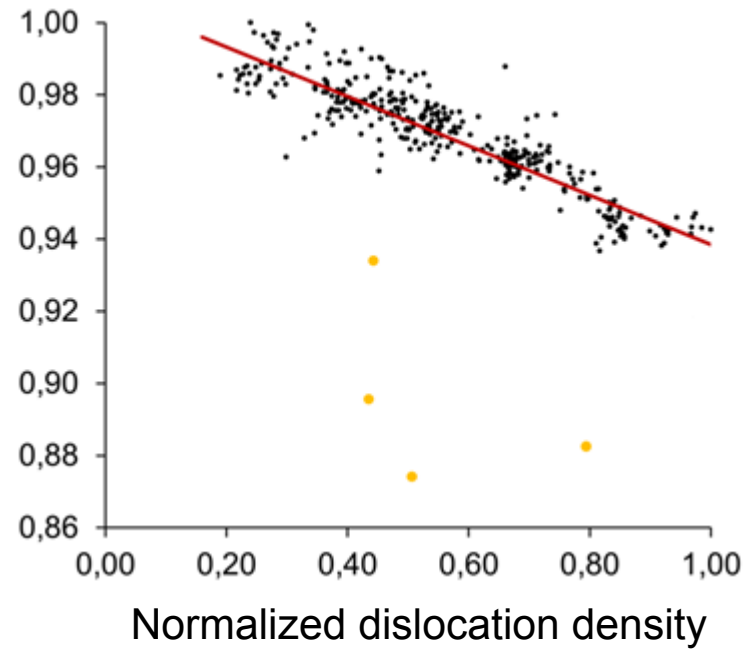
[Tarasov 1999]

# Dislocations and solar-cell efficiency

## Normalized dislocation density

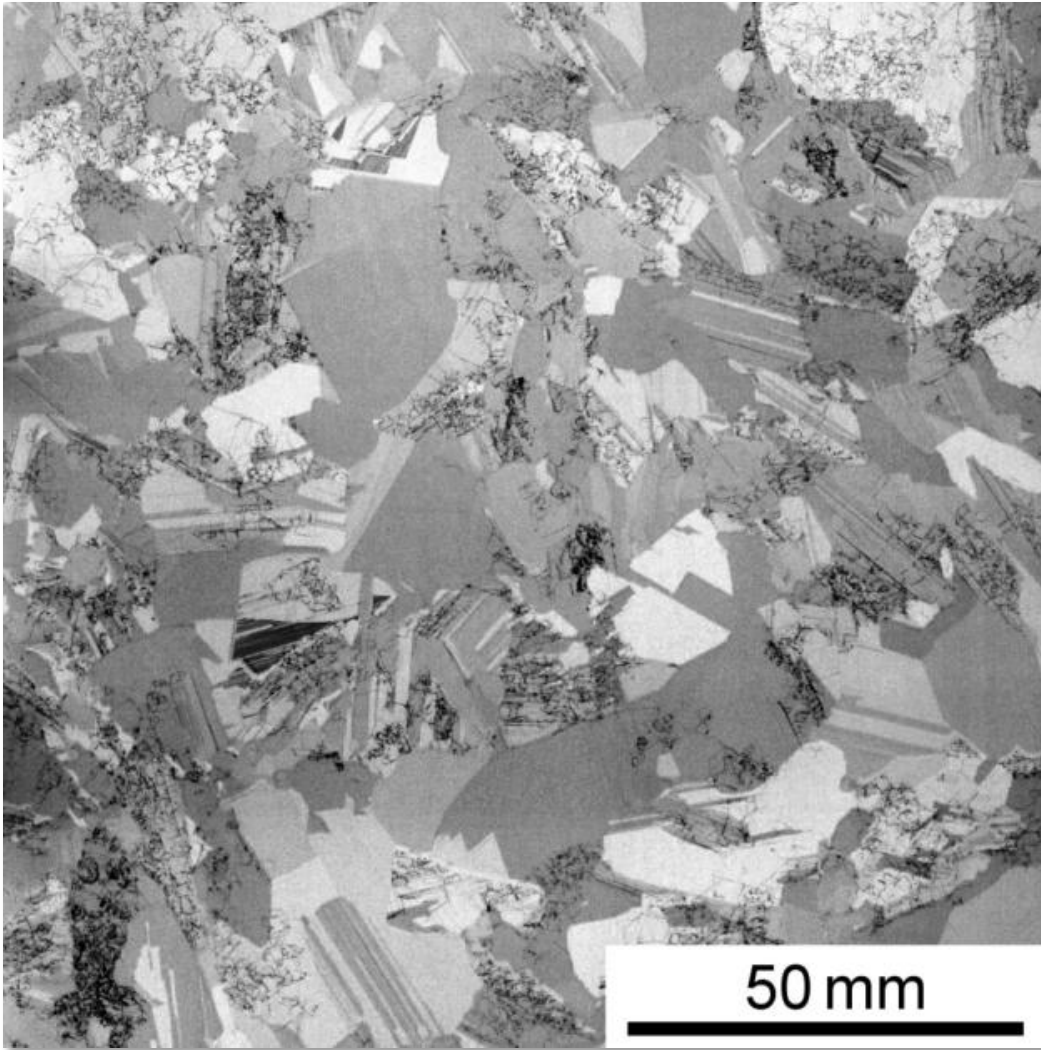


## Solar-cell efficiency $\eta$



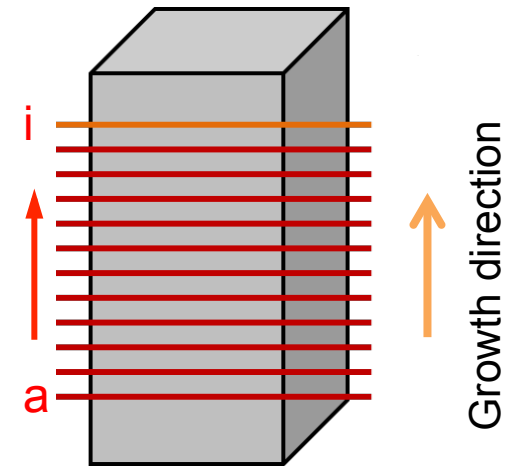
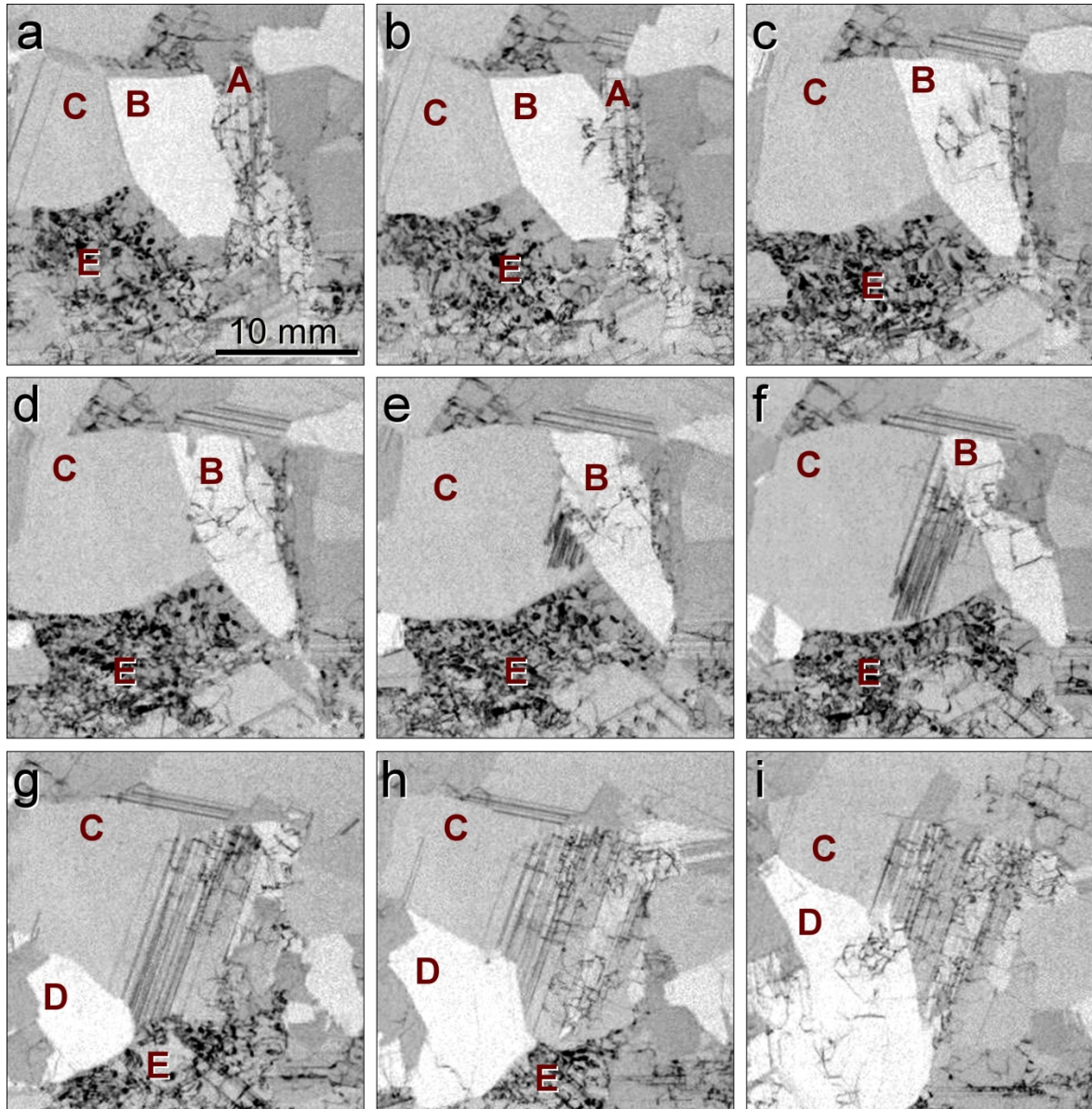


# Etched wafer surface

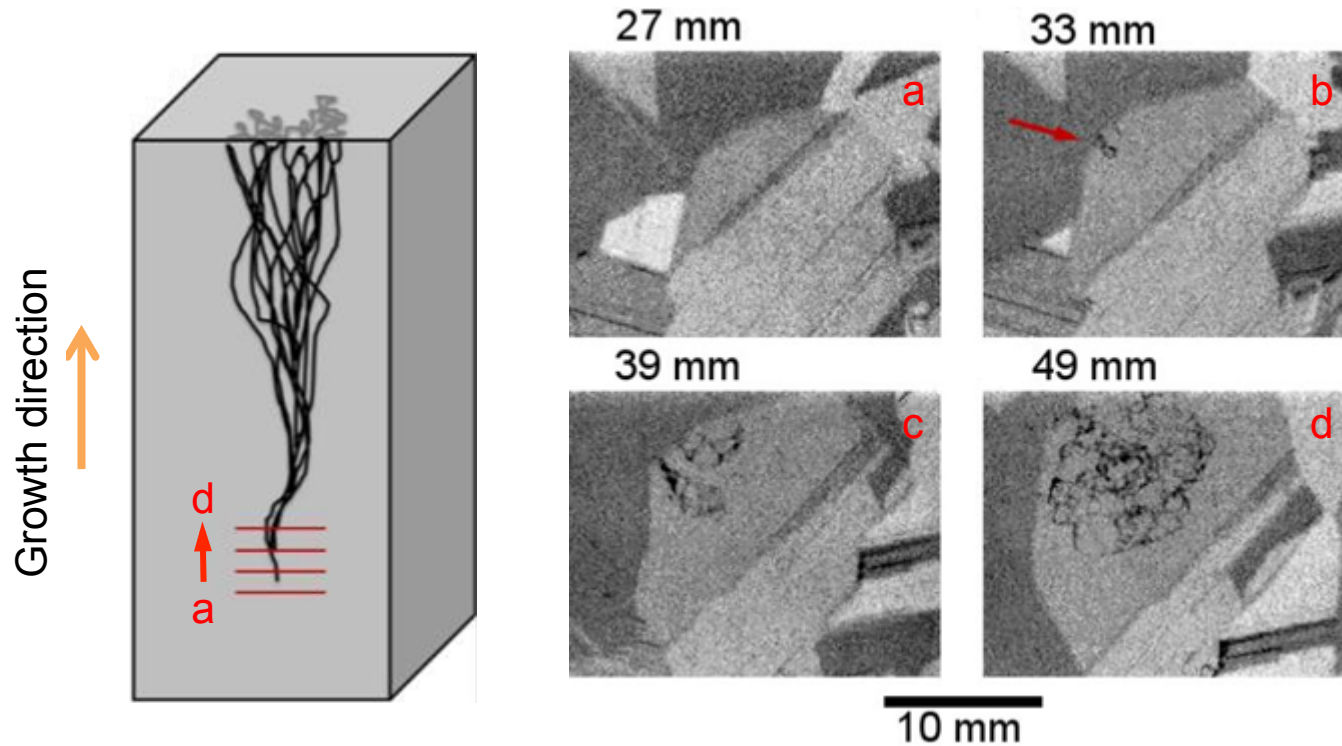


Typical defect distribution

# Change of defect distribution in the ingot



# Evolution of dislocations



- Dislocation clusters mainly generated at grain boundaries
- Atomistic source of the spontaneous dislocation generation not known

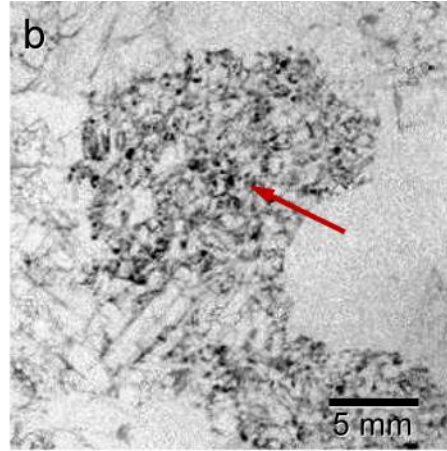
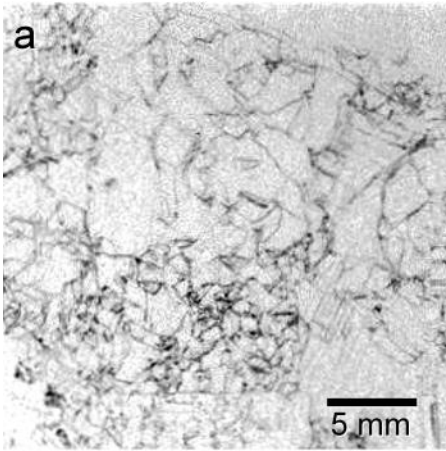


# Grain orientation effect

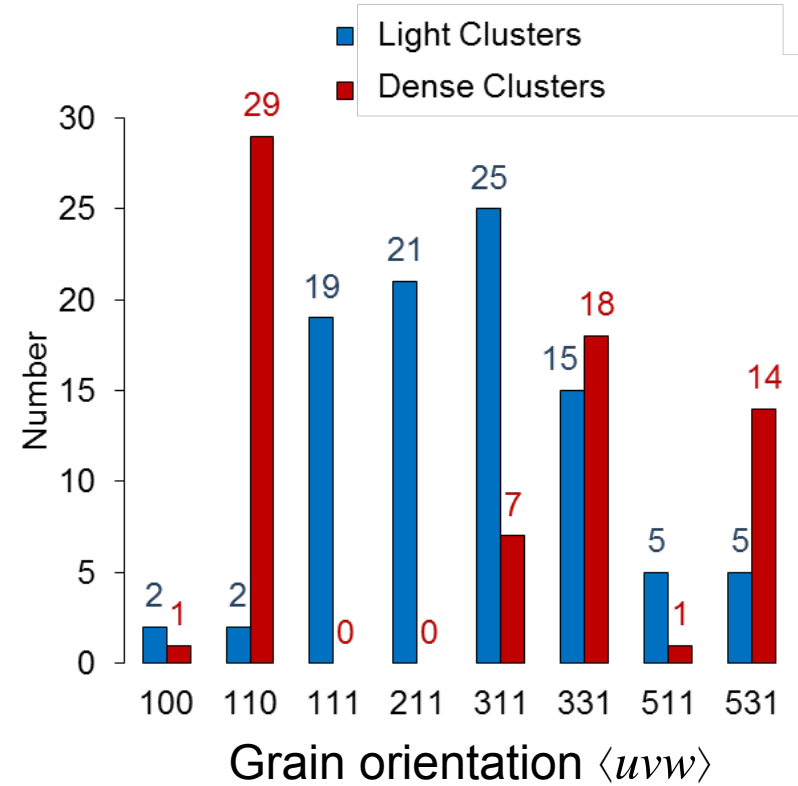
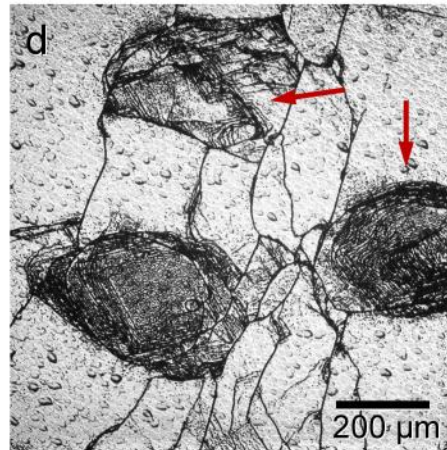
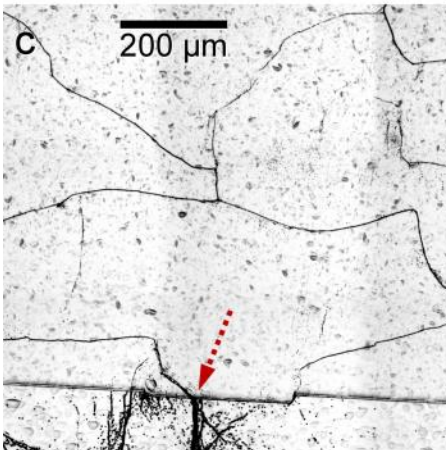
Light clusters (L)

Dense clusters (D)

Texture etch



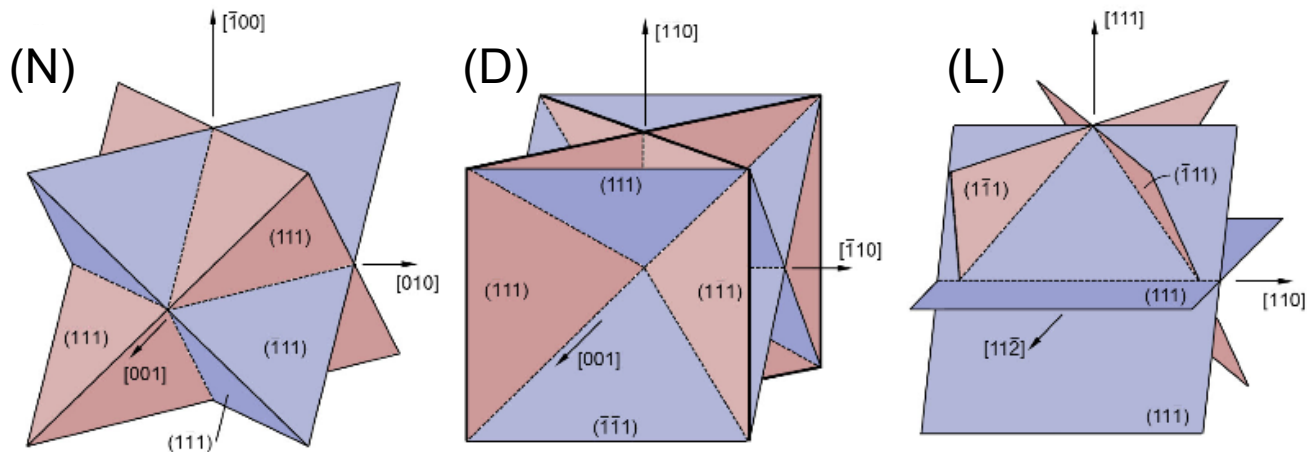
Wright-Jenkins etch



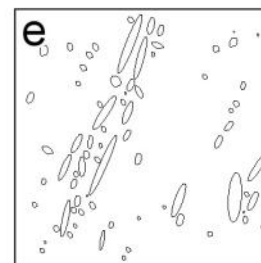
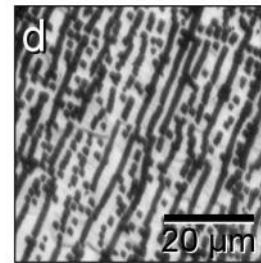
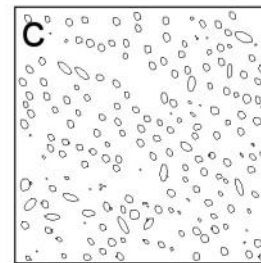
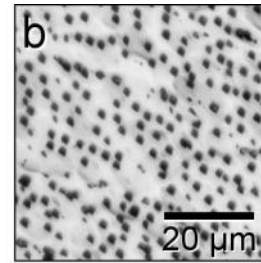
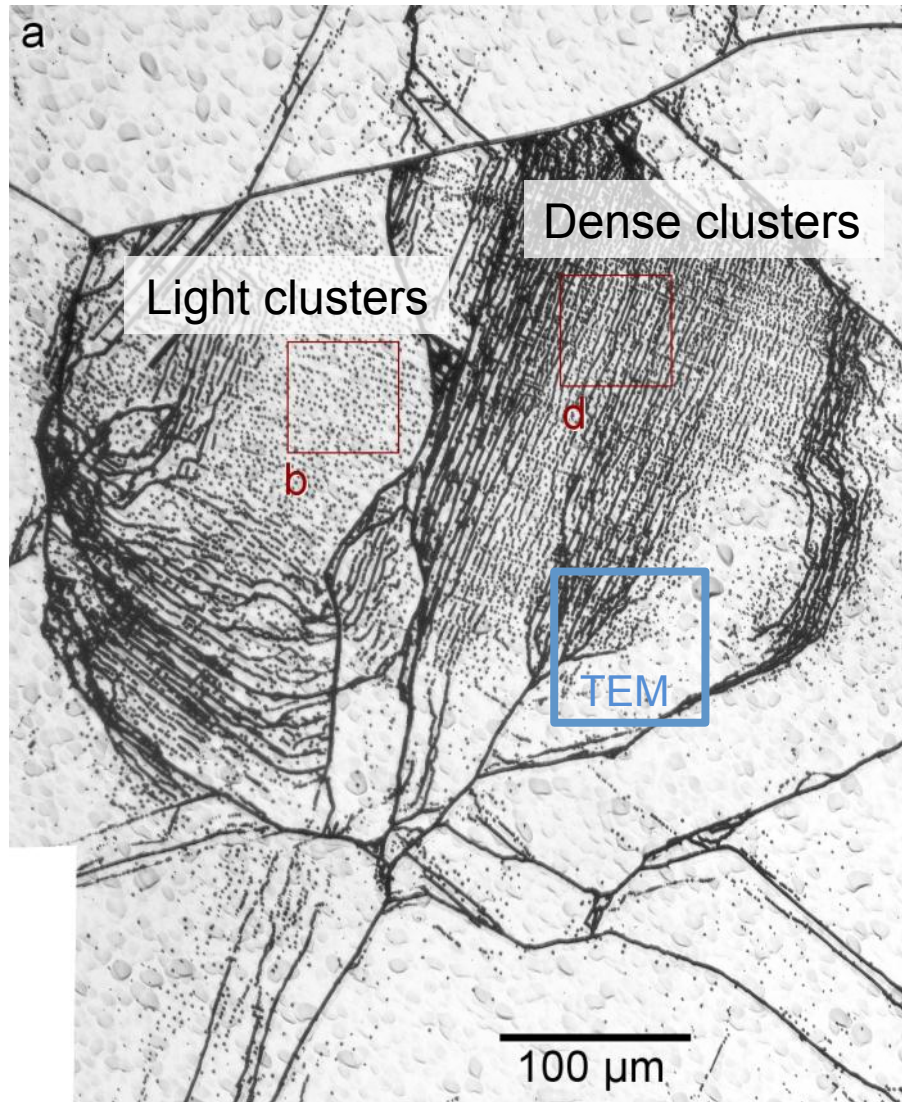


# Slip planes in relation to growth direction

- Angle  $\omega$  between growth direction and slip plane normal important for cluster formation
- (N) High  $\omega$  for all slip planes *or* moderate  $\omega$  for one plane:  
no clusters, *e. g.*  $\langle 100 \rangle$ ,  $\langle 511 \rangle$  grains
- (D) Low  $\omega$  for several slip planes:  
dense clusters, *e. g.*  $\langle 110 \rangle$ ,  $\langle 331 \rangle$ ,  $\langle 531 \rangle$  grains
- (L) Moderate  $\omega$  for several slip planes *or* low  $\omega$  for one plane:  
light clusters, *e. g.*  $\langle 111 \rangle$ ,  $\langle 211 \rangle$ ,  $\langle 311 \rangle$  grains



# Dislocation arrangements

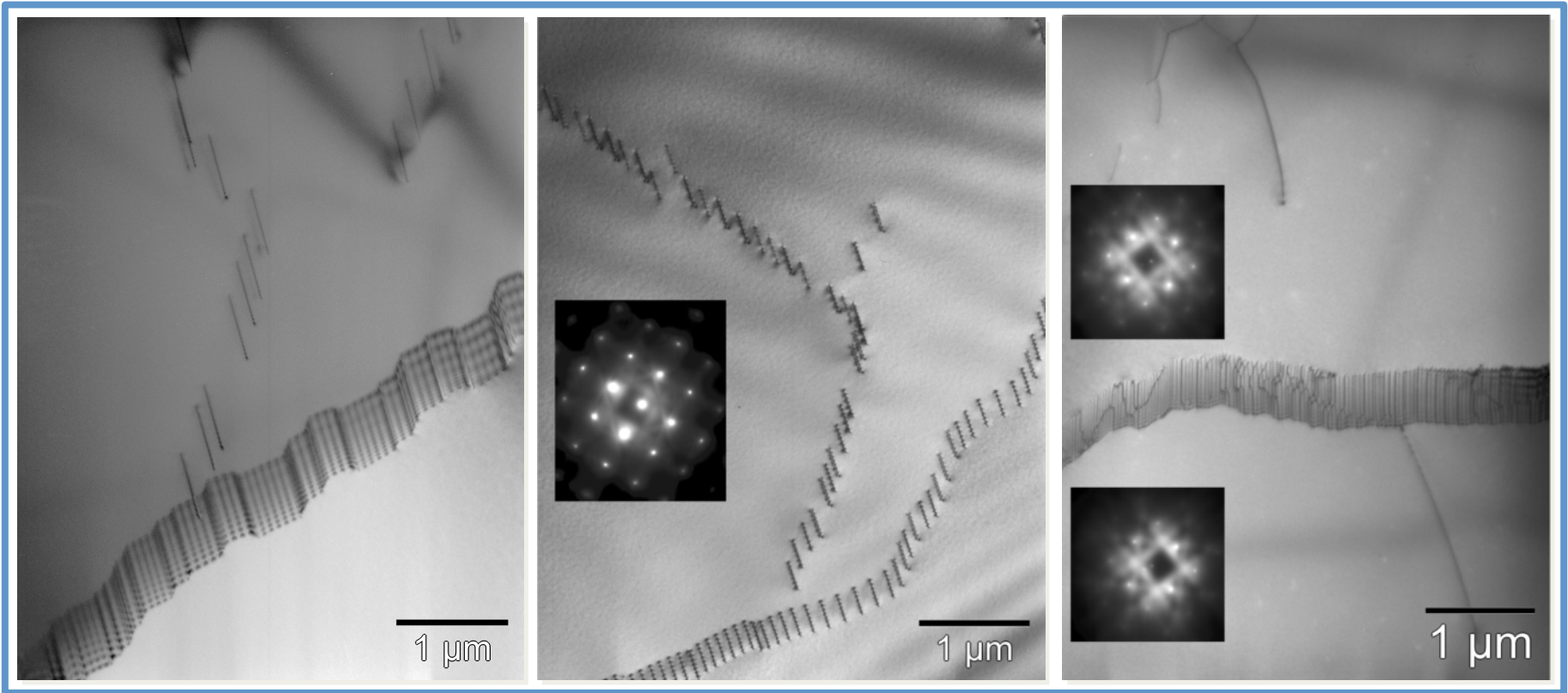


EPD  $\sim 1 \times 10^5 \text{ cm}^{-2}$

~~EPD  $2 \times 10^5 \text{ cm}^{-2}$~~

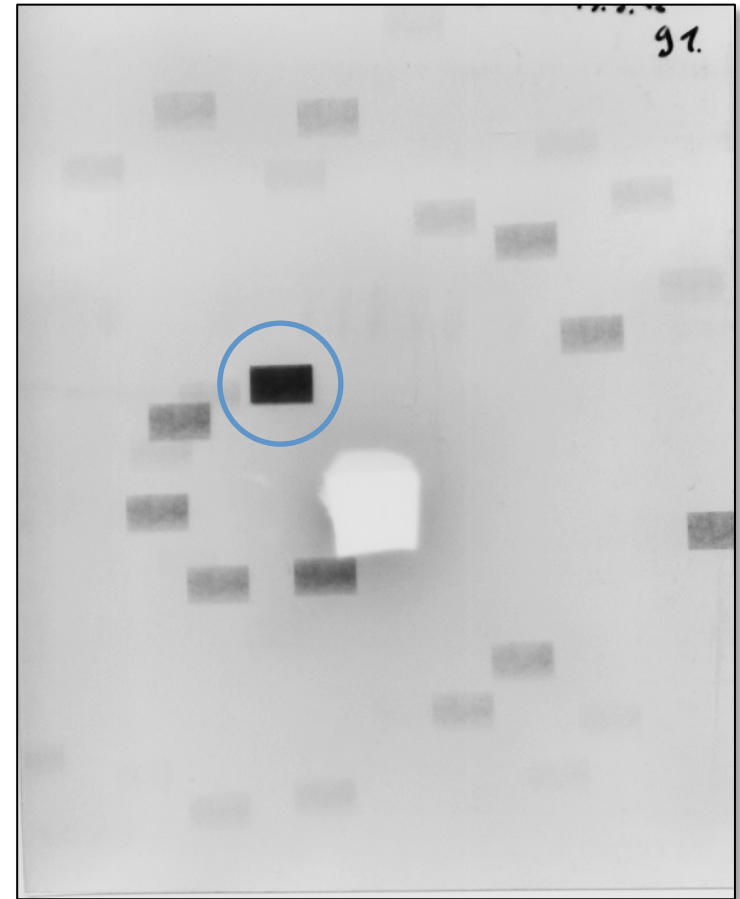
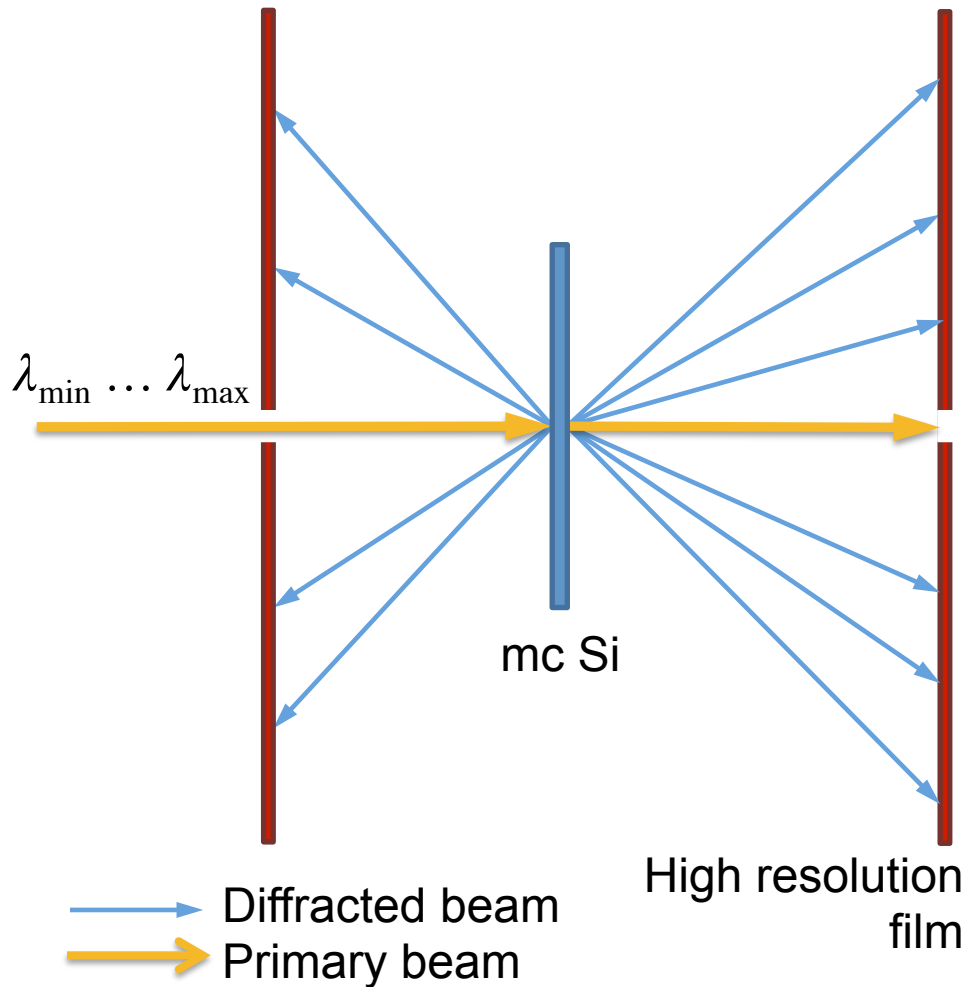
Too low for dislocation pile-ups/subgrain boundaries

# TEM of subgrain boundaries



- Dislocation distance  $h = 5 \dots 900 \text{ nm}$
- A preferred alignment dislocation arrangements exist, but not in relation to the orientation of the grains.

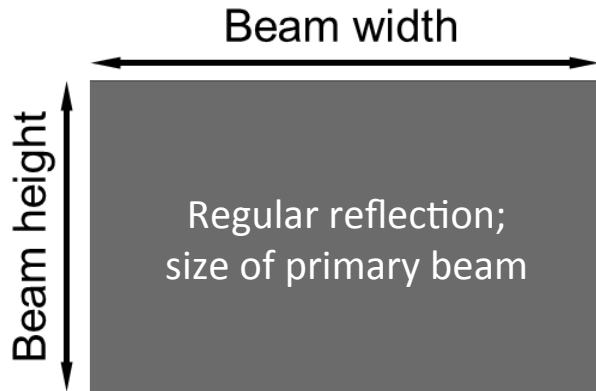
# White beam X-ray topography (WB-XRT)



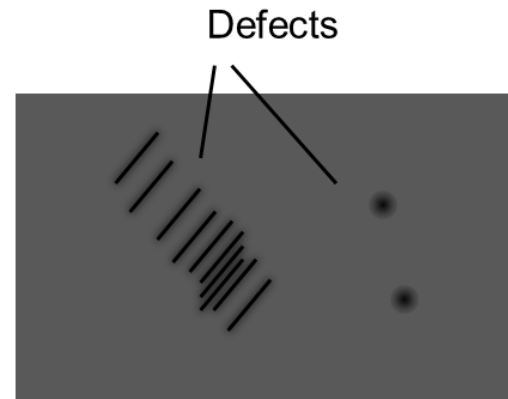
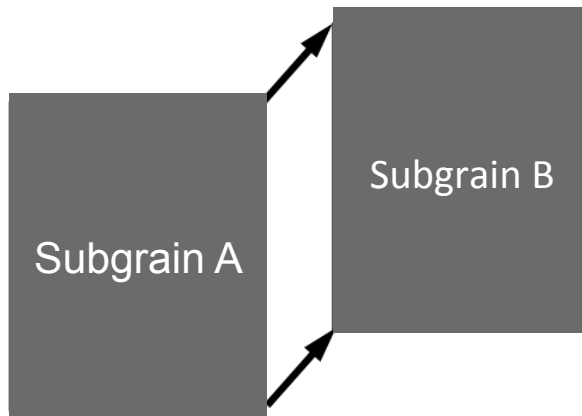
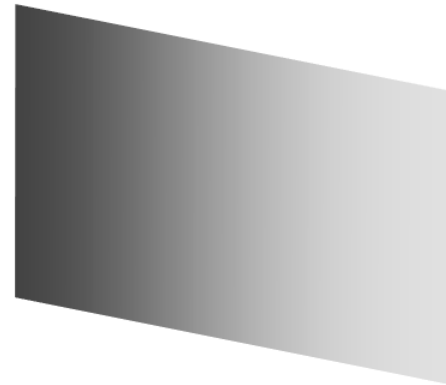
Laue pattern of the grain



# Interpretation of WB-XRT contrasts

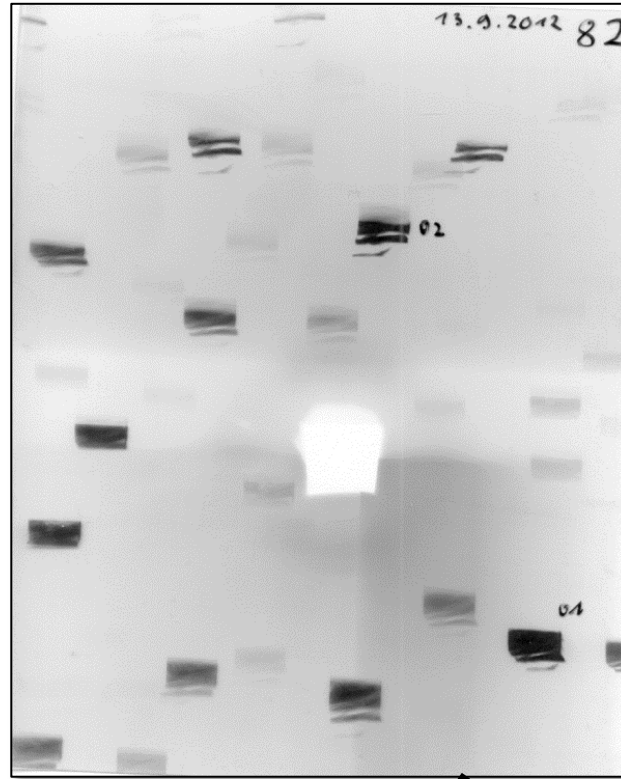


Continuous bending



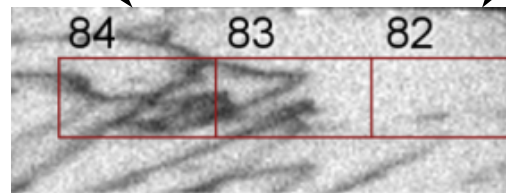
Splitting of the reflection  
due to subgrain boundary

# Splitting of reflections




WB-XRT Laue patterns

Growth direction



Band-band photoluminescence distribution

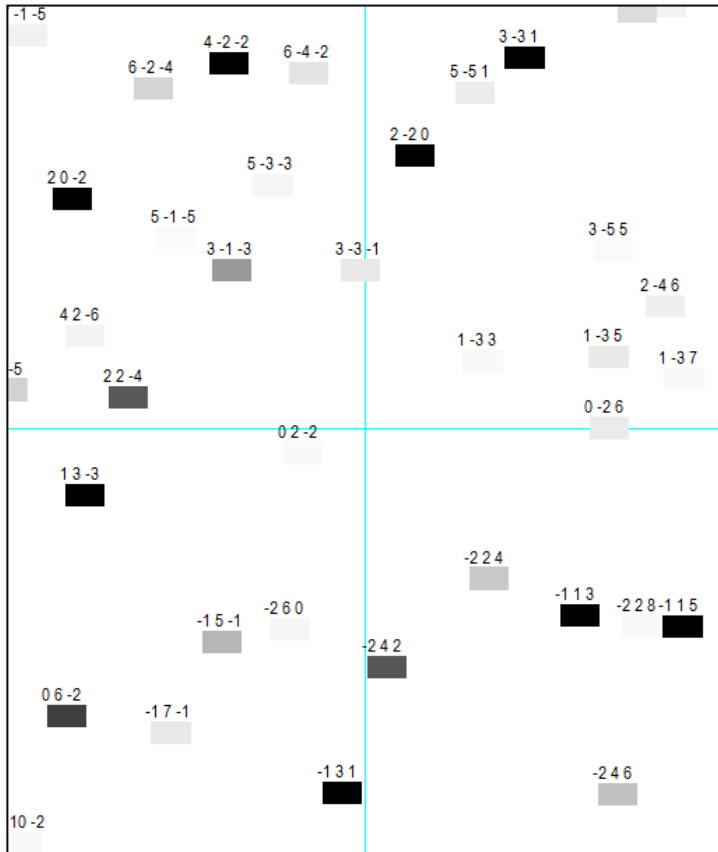
10 mm



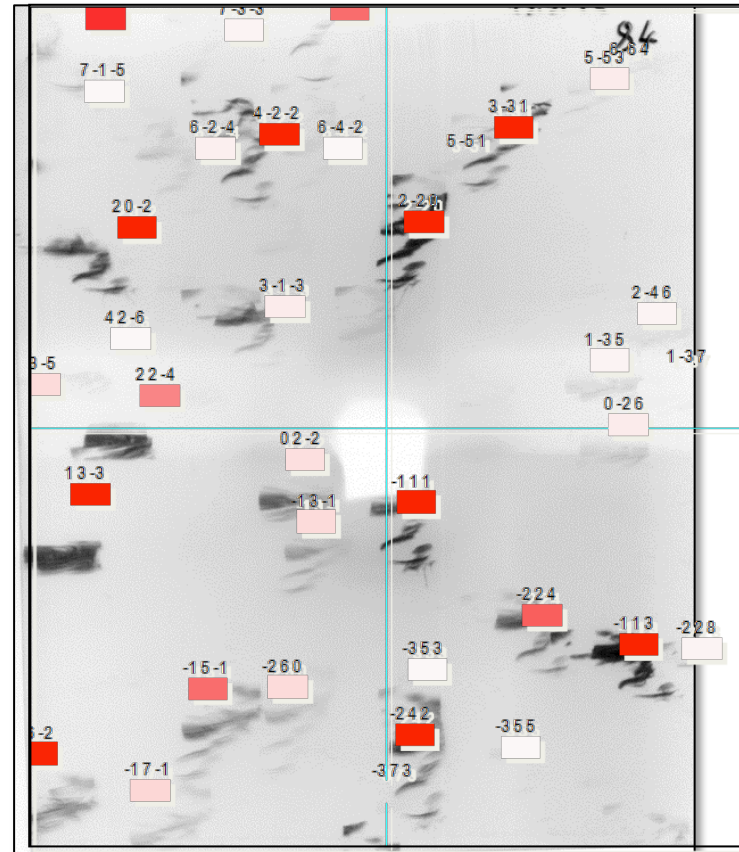
A black horizontal scale bar representing 10 mm.

# Tilt of subgrains

←  
Growth direction  $y$



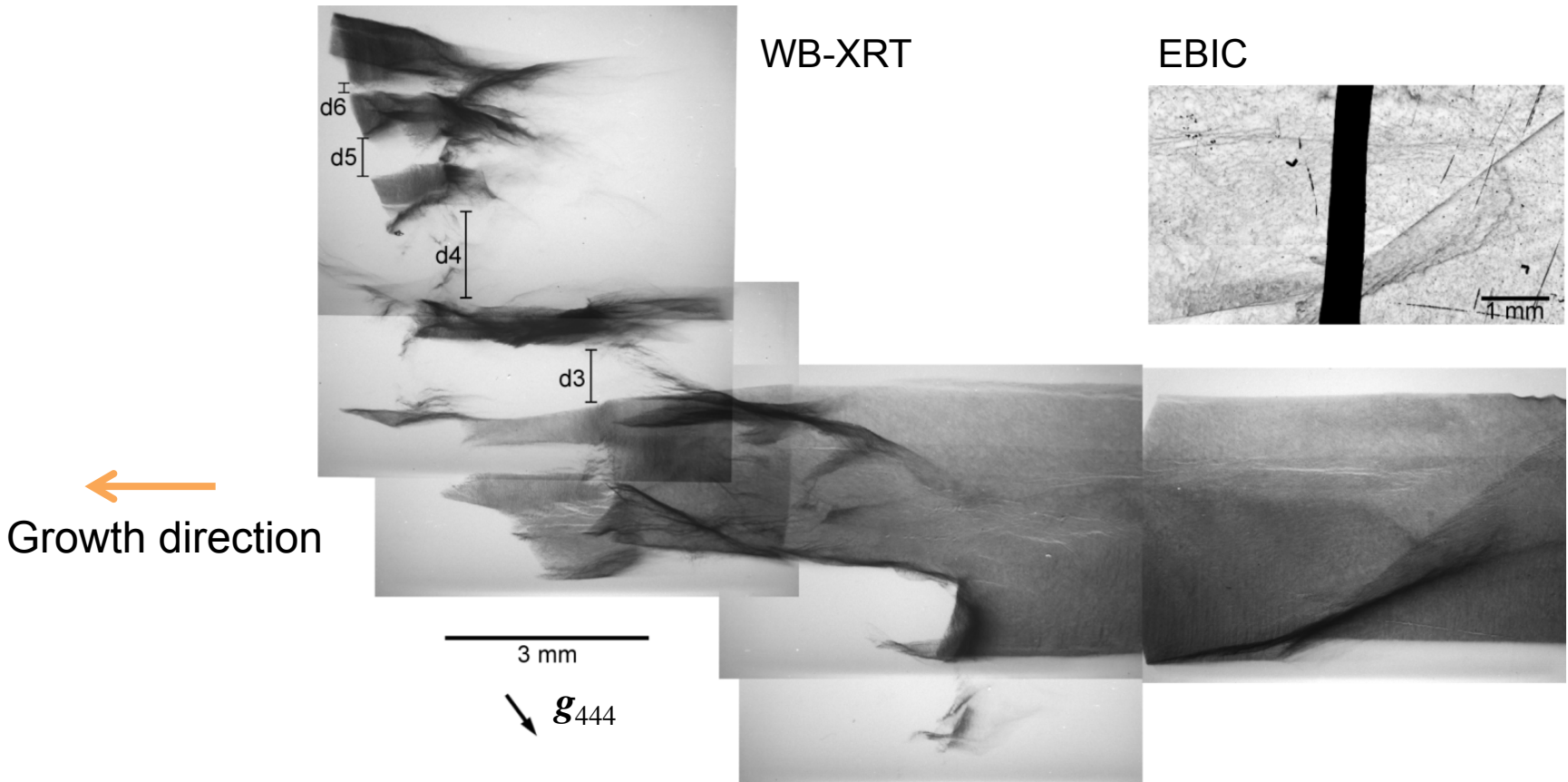
Simulation with **LauePT**



Simulation, rotated by 3° about  $y$

Subgrains are tilted about an axis parallel to the growth direction

# Relation of tilt and subgrain boundaries

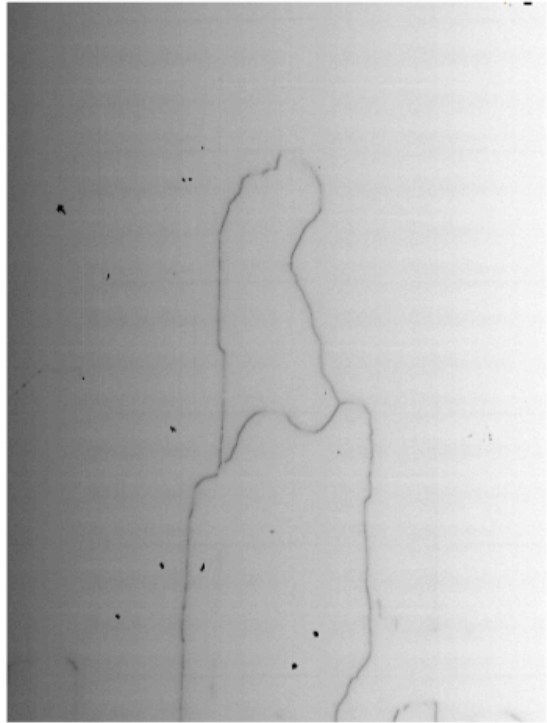


- Tilt =  $0.07^\circ$  (d6) ...  $0.3^\circ$  (d4)  $\rightarrow$  dislocation distance  $h = 800 \dots 30$  nm
- The increase in dislocation density in growth direction leads to a continuous generation of new subgrain boundaries.

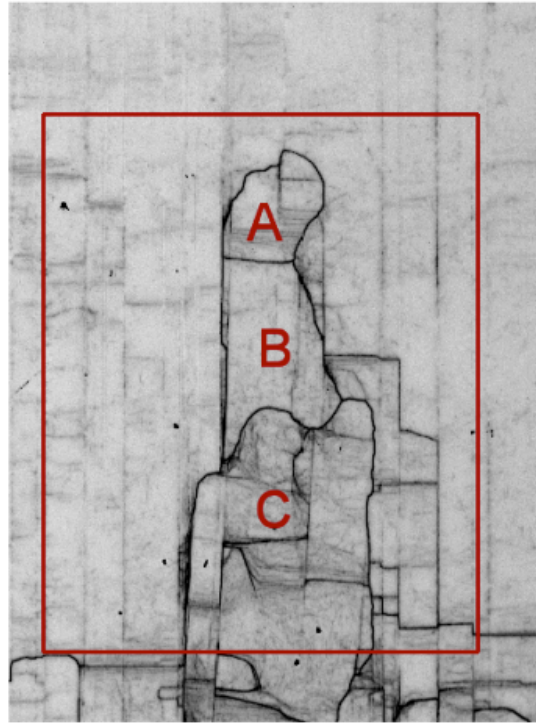


# EBIC and X-ray topography

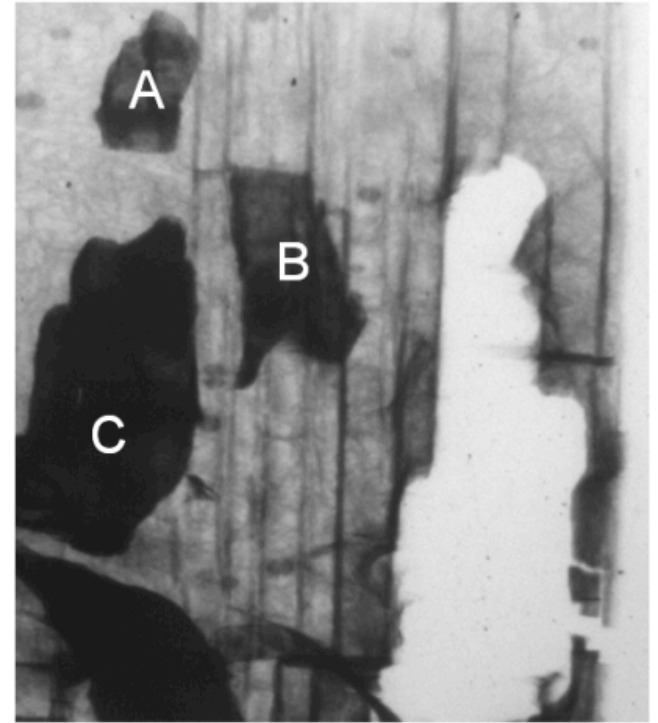
EBIC at RT



EBIC at 77 K



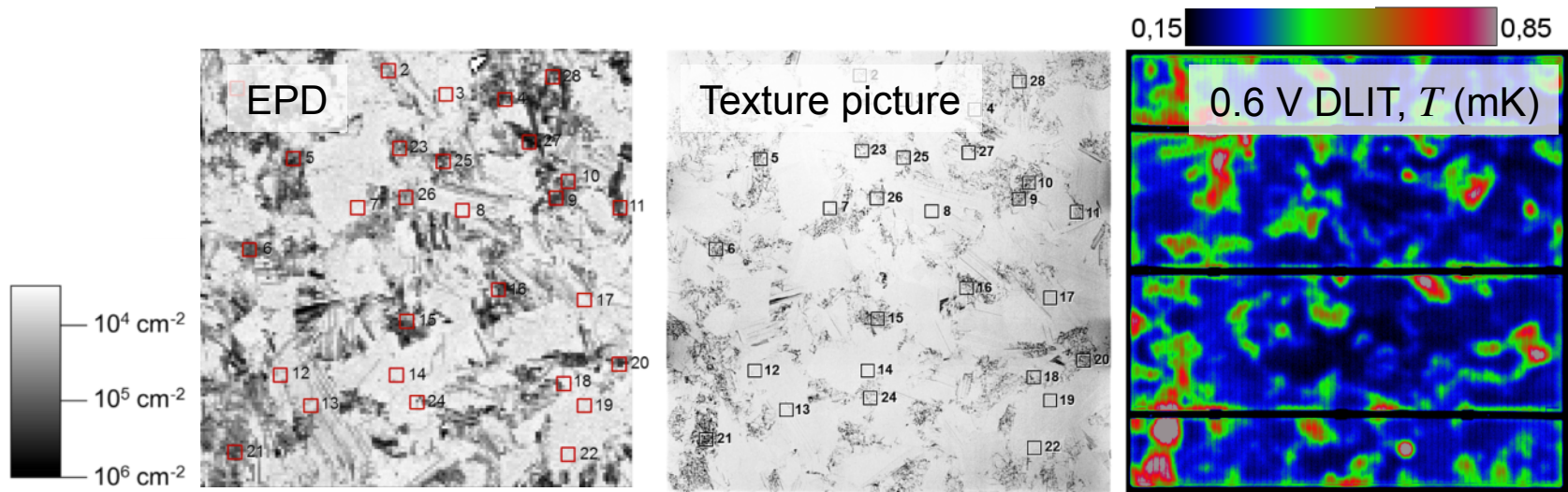
WB-XRT



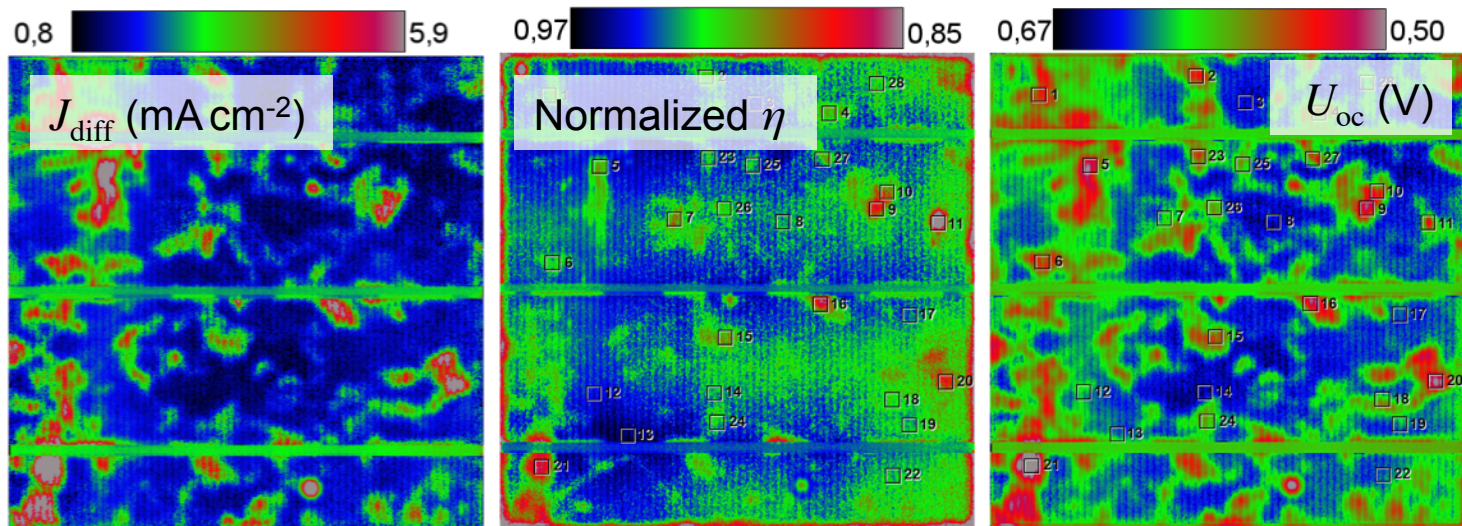
1 mm



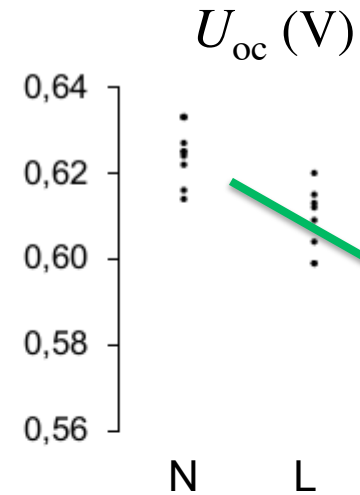
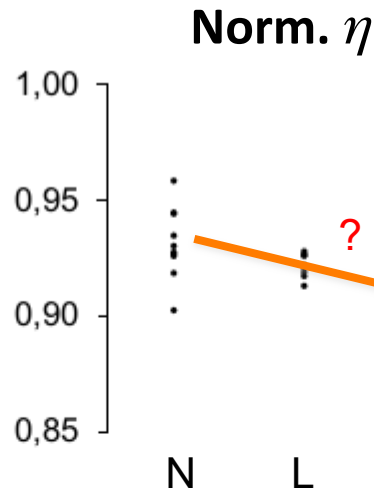
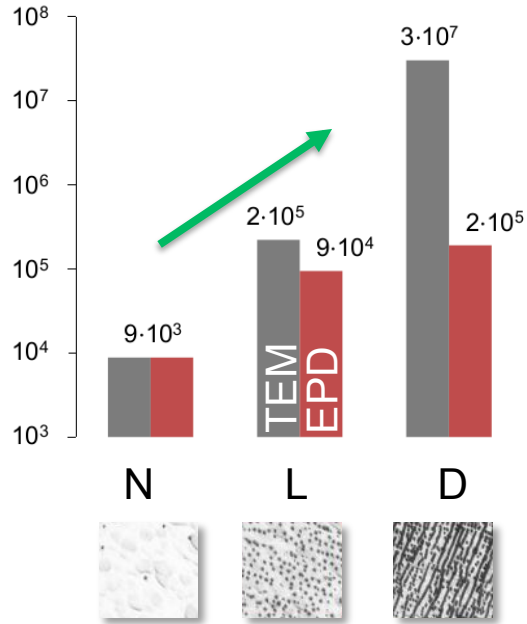
# Dark lock-in thermography (DLIT)



Simulation with **Local IV**  
 [Breitenstein 2012]



# Correlation analysis

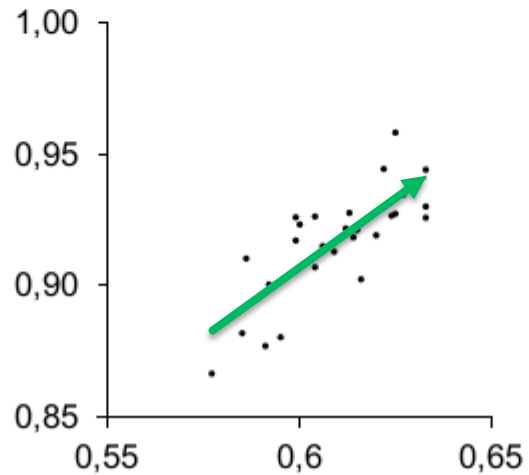


No clusters

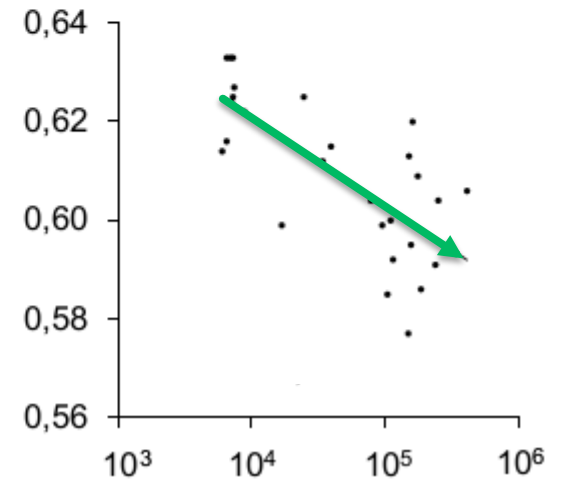
Light dislocation clusters

Dense clusters  
(pile ups/small angle GBs)

Norm.  $\eta$  vs  $U_{oc}$  (V)

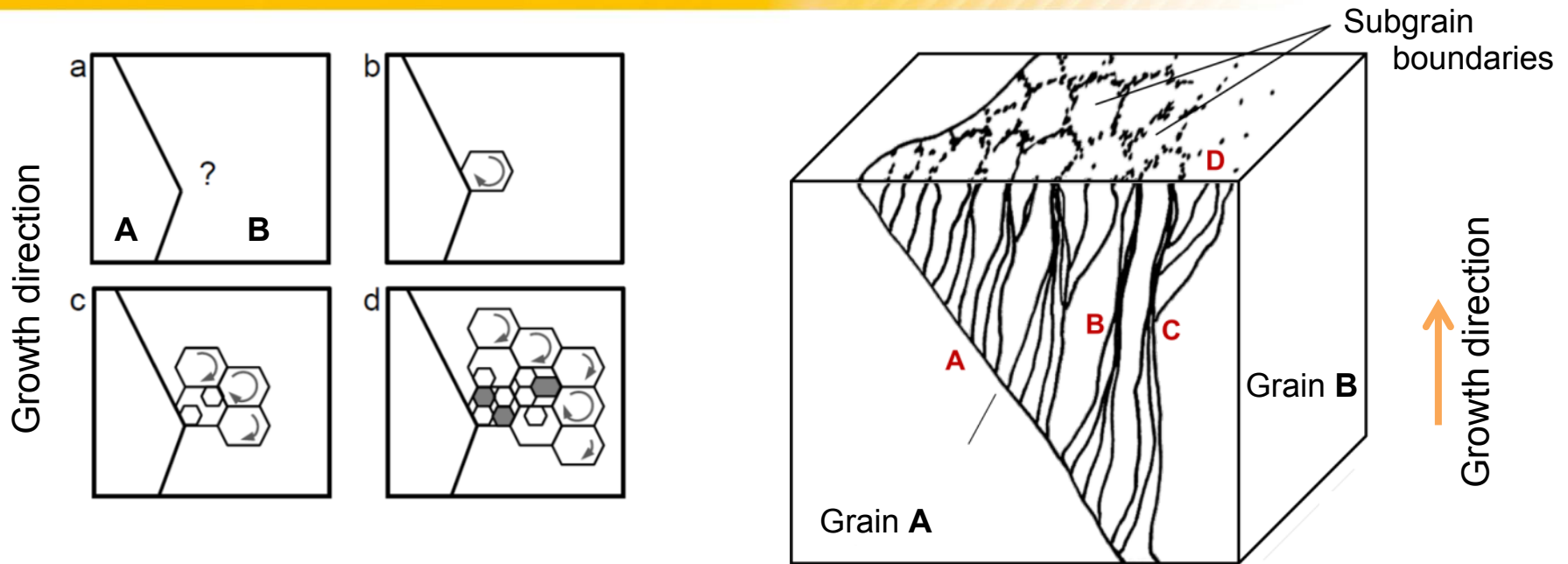


$U_{oc}$  (V) vs EPD ( $\text{cm}^{-2}$ )





# Conclusions

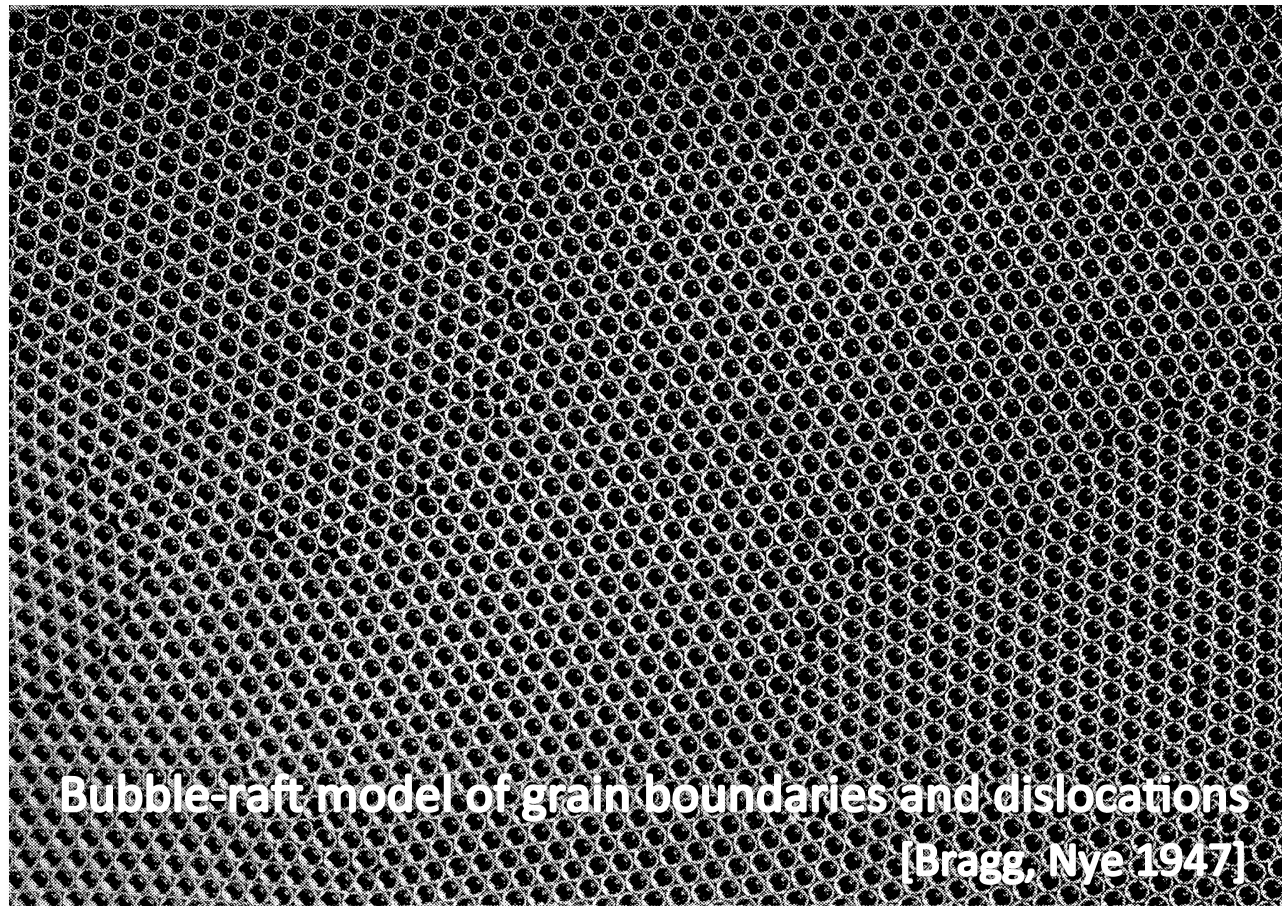


## Evolution of dislocation pattern

- Initial generation, mostly at grain boundaries
- Inhomogeneous dislocation distribution on different scales, (N)  $\rightarrow$  (L)
- Multiplication, pile-up and restructuring to subgrain boundaries, (D)
- Dense dislocation clusters with dominant influence on solar cell efficiency



# Žěkujom se wutšobnje.



# References

- K Arafune *et al*: Phys. B **376** (2006) 236.
- L Bragg, JF Nye: Proc Royal Soc Lond Ser A (1947) 474.
- O Breitenstein: Sol En Mater Sol Cells **107** (2012) 381.
- D Oriwol *et al*: Acta Mater **61** (2013) 6903.
- I Tarasov *et al*: Phys. B **273-274** (1999) 549.